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# Development of Granular Metals for High Voltage Applications

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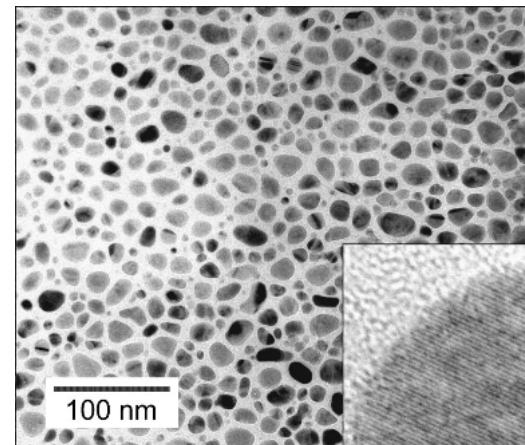
# Outline

What are granular metals?

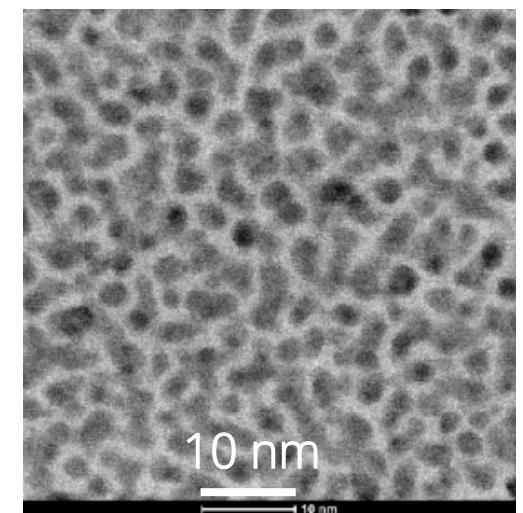
How does their nanostructure influence transport properties?

How can we optimize this nanostructure for high voltage applications?

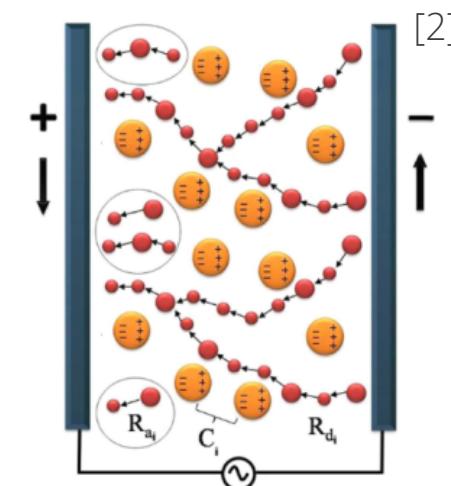
Summary



Cobalt/yttria-stabilized  
 $\text{ZrO}_2$  (Co/YSZ) [1]



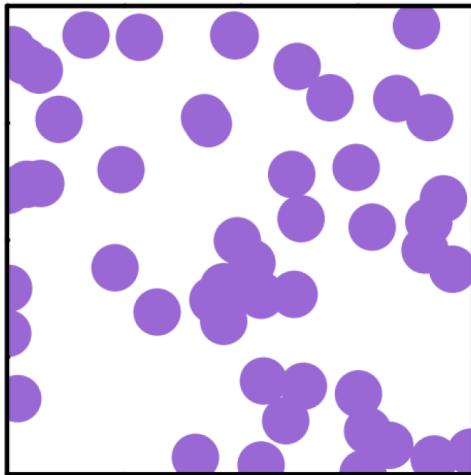
Pd/YSZ (Sandia)



# Granular metals comprise metal islands embedded in an insulating matrix

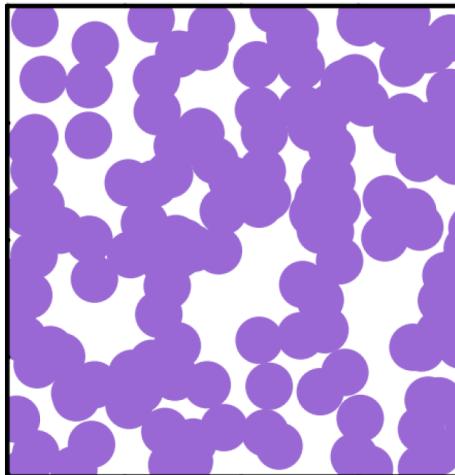
Dielectric

$$\phi < \phi_c$$



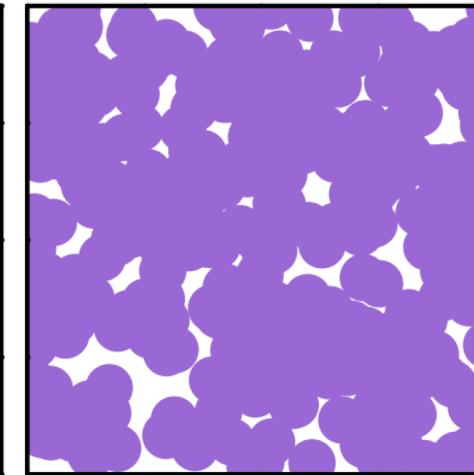
Percolation threshold

$$\phi \approx \phi_c$$



Metal

$$\phi > \phi_c$$



Common metals

Ag, Au, Ni, Pd, Co, Fe

Common insulators

$\text{SiO}_2$ ,  $\text{Al}_2\text{O}_3$ , yttria-stabilized zirconia (YSZ)

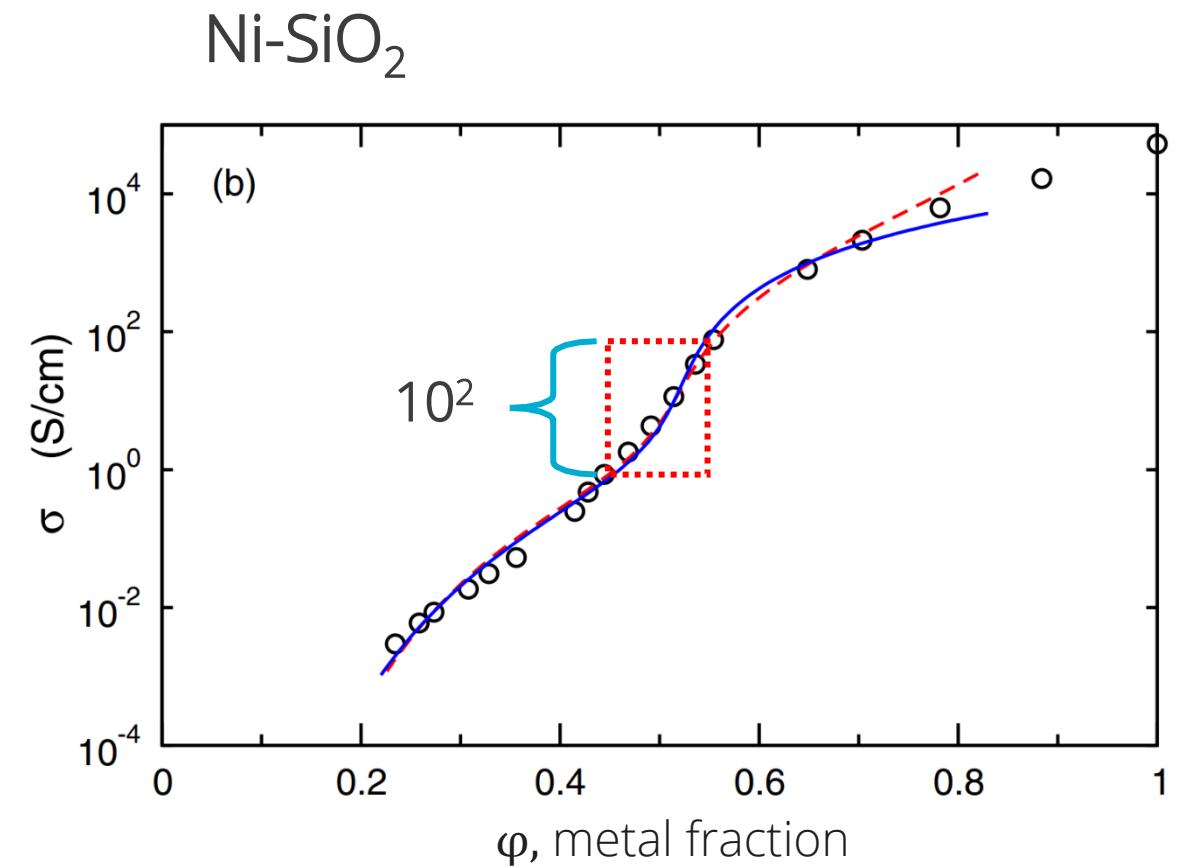
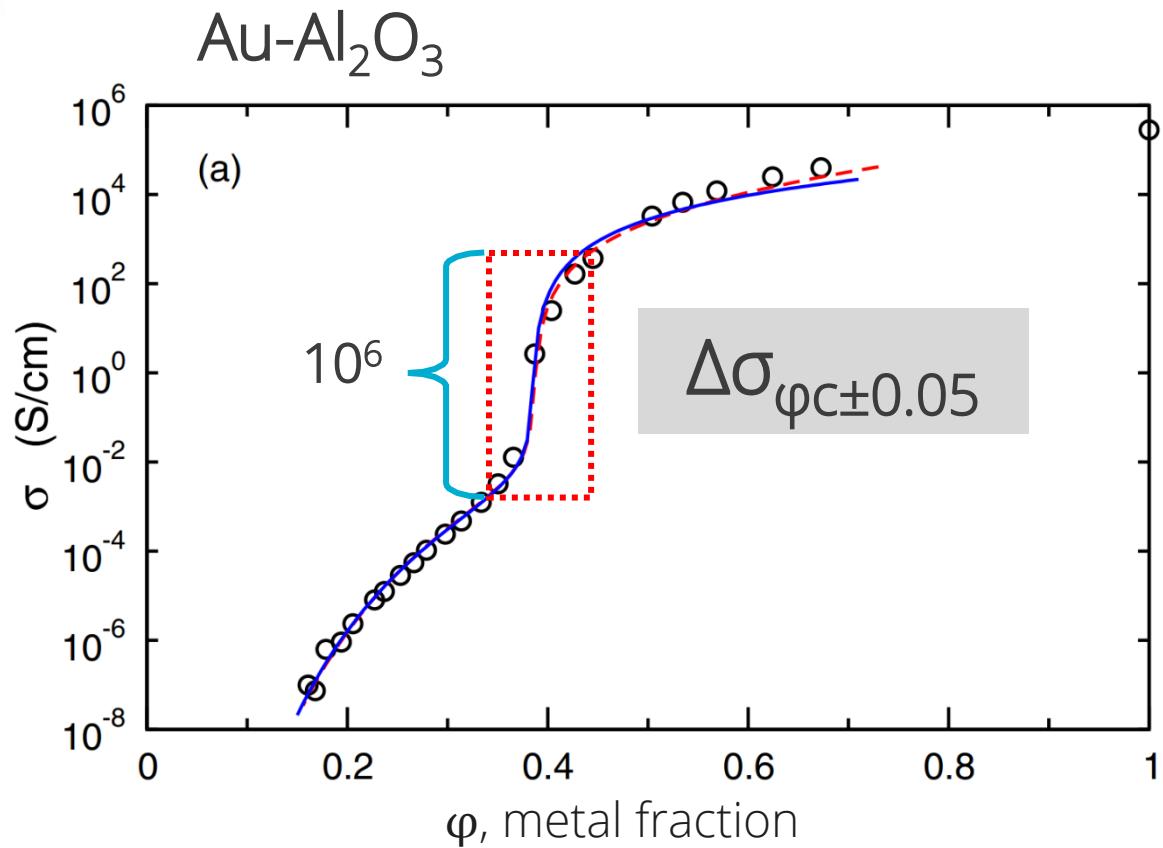
$$\sigma \propto \exp\left(-1.41 \frac{D}{\xi \varphi^{\frac{1}{3}}}\right)$$

$$\sigma \approx \sigma_0 \left( \frac{1}{1 - \frac{D}{\xi \varphi}} \right)^2$$

Island diameter,  $D \sim 1\text{--}10 \text{ nm}$

Tunneling decay length,  $\xi \sim 0.1\text{--}1 \text{ nm}$

# Similar granular metal systems exhibit large variances in dc conductivity

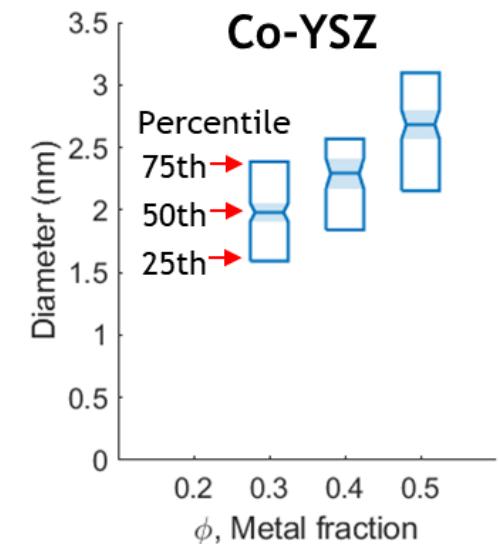
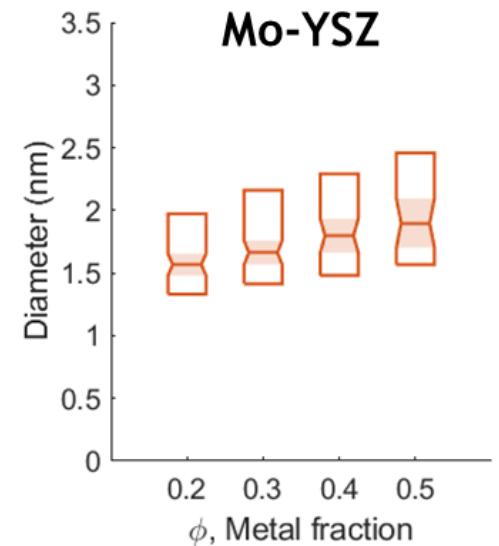
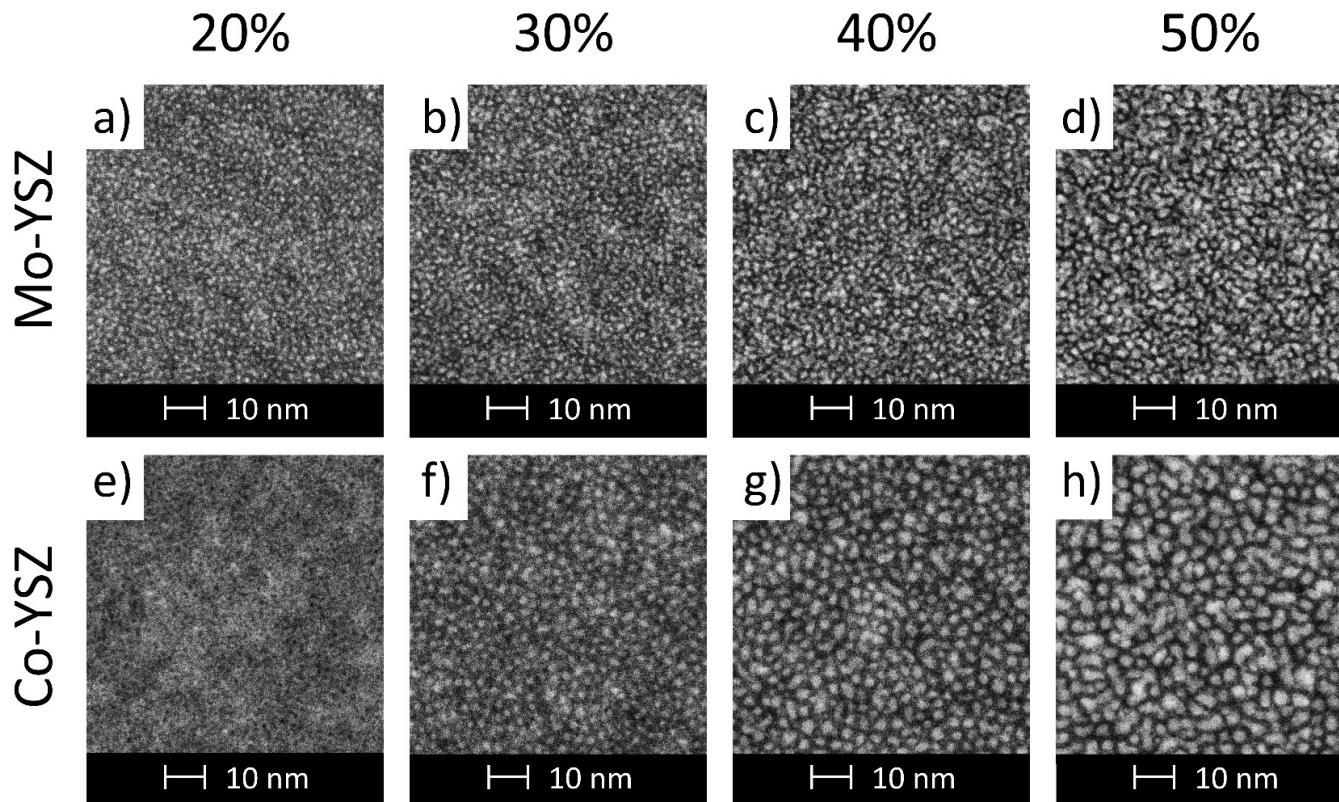
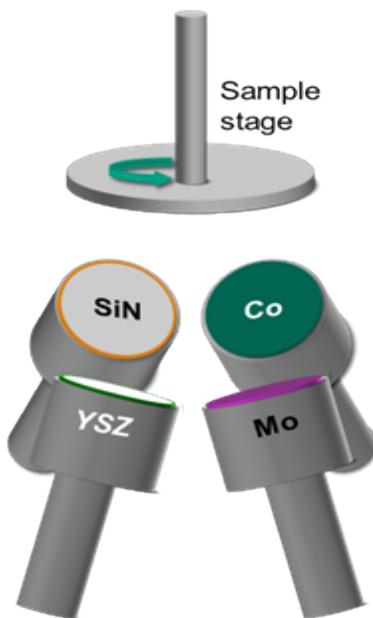


# Optimized rf sputtering geometry, power, and pressure to grow well-controlled granular metal films

Vary metal/ceramic ratio by adjusting the rf power of the metal while keeping insulator power constant.

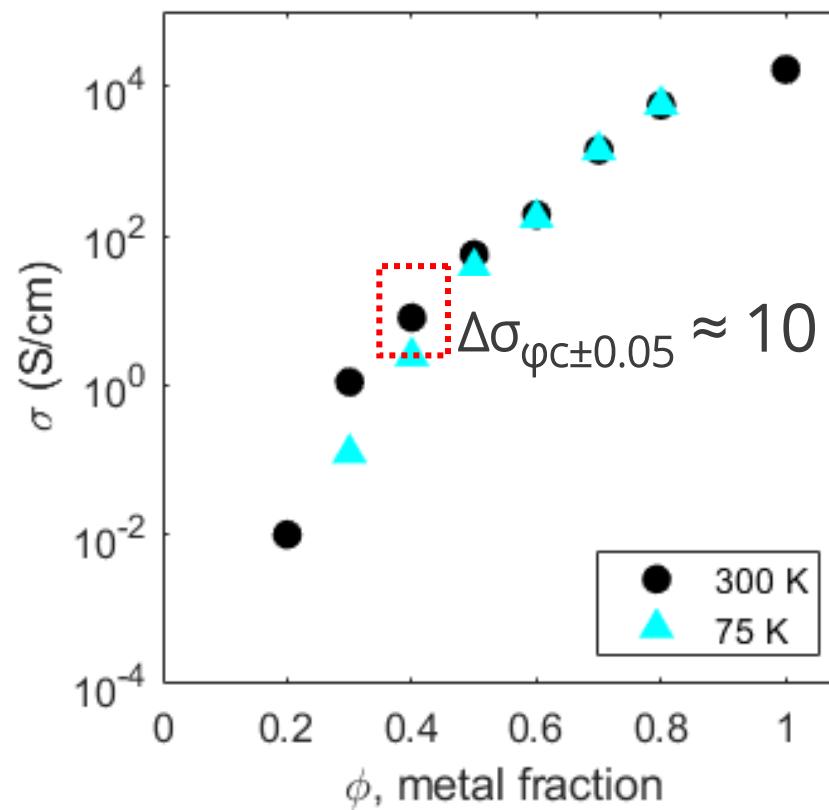
Lower rf power (<100 W) minimizes in-situ annealing during deposition.

5 mTorr argon

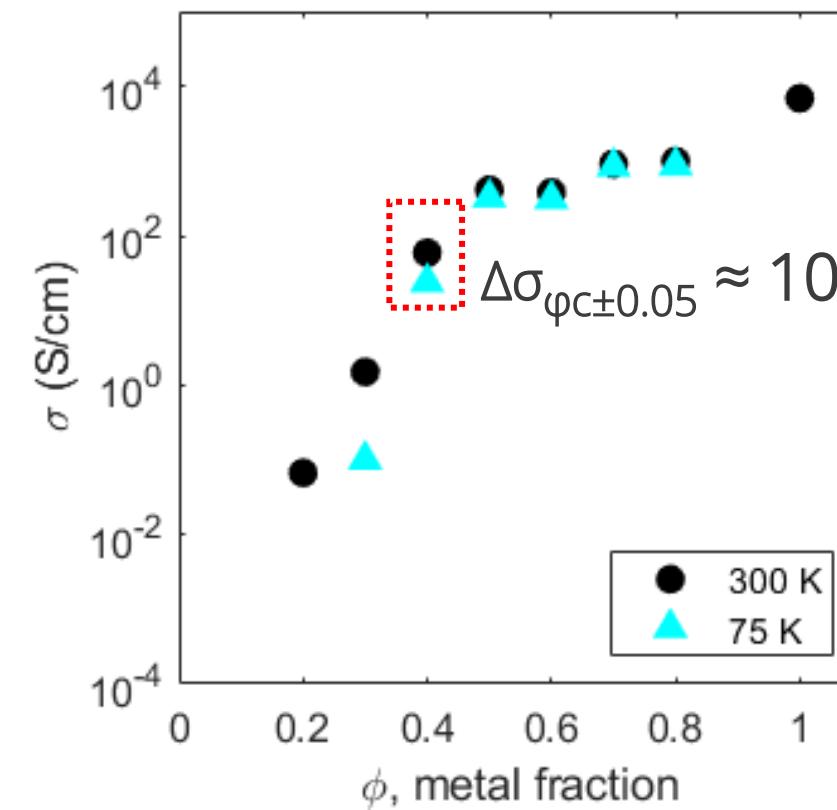


# Conductivity curves for Co-YSZ and Mo-YSZ are characteristic of GMs

## Co-YSZ



## Mo-YSZ

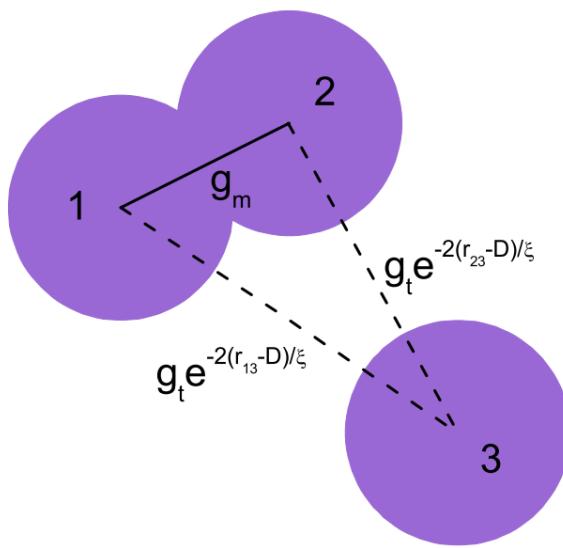


$$\sigma(T) \propto \exp\left(-\sqrt{\frac{T_0}{T}}\right)$$

Weak transition between dielectric and metallic regimes;  $\Delta\sigma \approx 10$  at the percolation threshold

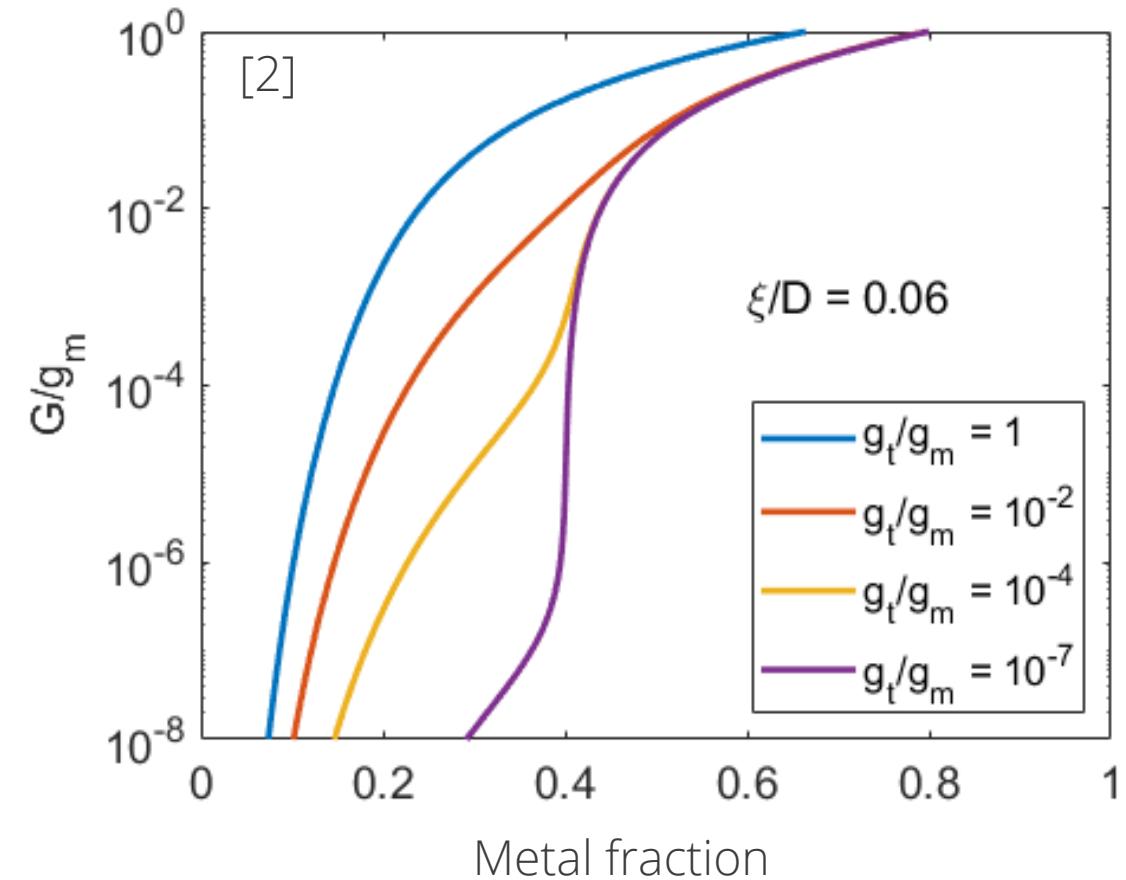
# Conductivity change at the percolation threshold dependent on interface interactions

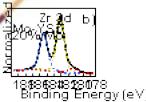
Grimaldi<sup>1</sup> proposed that conductivity depends on the ratio of tunneling ( $g_t$ ) and metal ( $g_m$ ) conductivities.



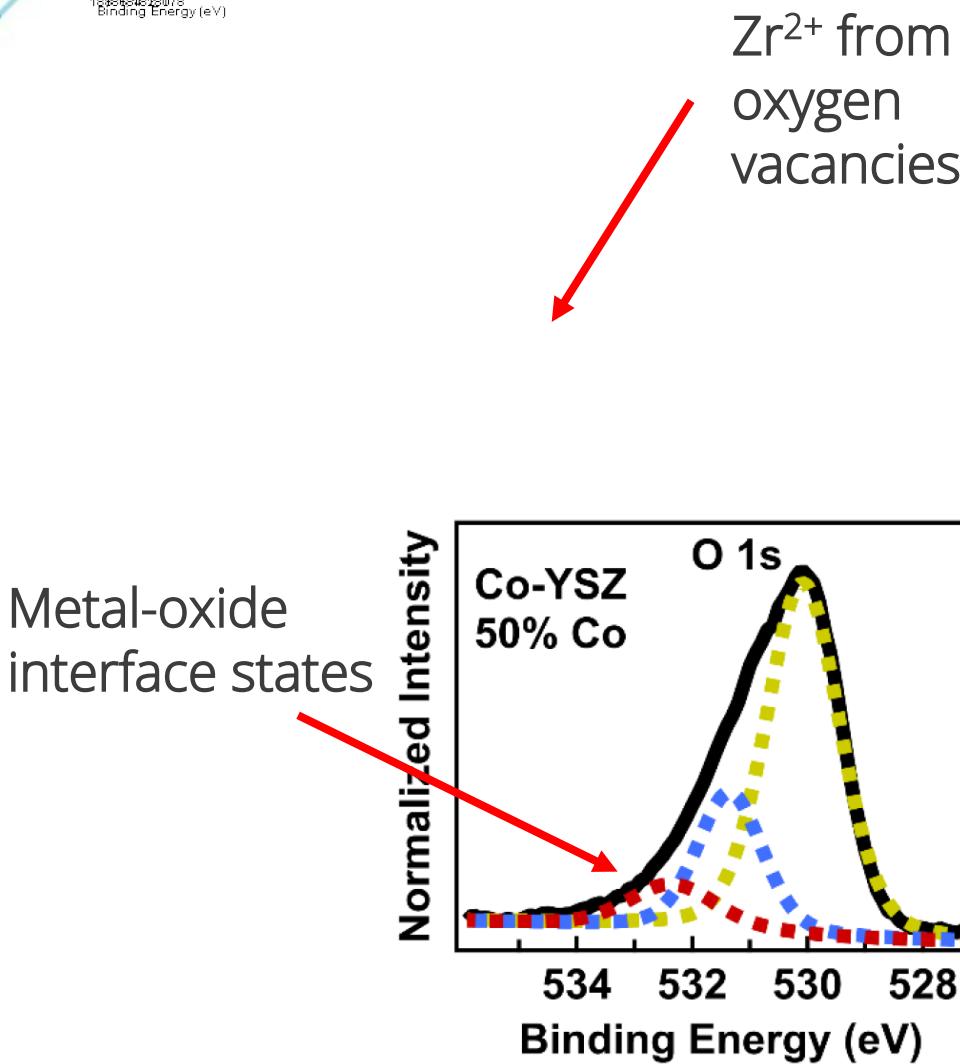
Island diameter  
 $D \sim 1\text{--}10\text{ nm}$   
 Tunneling decay length  
 $\xi \sim 0.1\text{--}1\text{ nm}$

$$\frac{\left(\frac{\varphi}{\varphi_c}\right) g_m^{1/t}}{G^{1/t} + g_m^{1/t}} + 4\varphi \left\{ \left[ 1 + \frac{\xi}{2D} \ln \left( \frac{g_t + G}{G} \right) \right]^3 - 1 \right\} = 1$$





# Interface interactions explain conductivity trends



Reference	Metal	Insulator	$\Delta\sigma_{\varphi_c \pm 0.05}$
This work	Mo	YSZ	$10^1$
This work	Co	YSZ	$10^1$
Stogny <sup>1</sup>	Co	Al <sub>2</sub> O <sub>n</sub>	$10^2$
Niklasson <sup>2</sup>	Co	Al <sub>2</sub> O <sub>3</sub>	$10^7$
Barzilai <sup>3</sup>	Co	SiO <sub>2</sub>	$10^2$
Zhu <sup>4</sup>	Fe	Al <sub>2</sub> O <sub>3</sub>	$10^2$
Aronzon <sup>5</sup>	Fe	SiO <sub>2</sub>	$10^2$
Honda <sup>6</sup>	Fe	SiO <sub>2</sub>	$10^3$
Gittleman <sup>7</sup>	Ni	SiO <sub>2</sub>	$10^2$
Toker <sup>8</sup>	Ni	SiO <sub>2</sub>	$10^2$
Abeles <sup>9</sup>	Ni	SiO <sub>2</sub>	$10^2$
Milner <sup>10</sup>	Ni	SiO <sub>2</sub>	$10^4$
Abeles <sup>11</sup>	W	Al <sub>2</sub> O <sub>3</sub>	$10^2$
Wei <sup>12</sup>	Ag	SnO <sub>2</sub>	$10^1$
Balberg <sup>13</sup>	Ag	Al <sub>2</sub> O <sub>3</sub>	$10^2$
Cohen <sup>14</sup>	Ag	SiO <sub>2</sub>	$10^4$
Priestley <sup>15</sup>	Ag	SiO <sub>2</sub>	$10^5$
Abeles <sup>9</sup>	Au	Al <sub>2</sub> O <sub>3</sub>	$10^6$
Cohen <sup>14</sup>	Au	SiO <sub>2</sub>	$10^4$
McAlister <sup>16</sup>	Au	SiO <sub>2</sub>	$10^8$

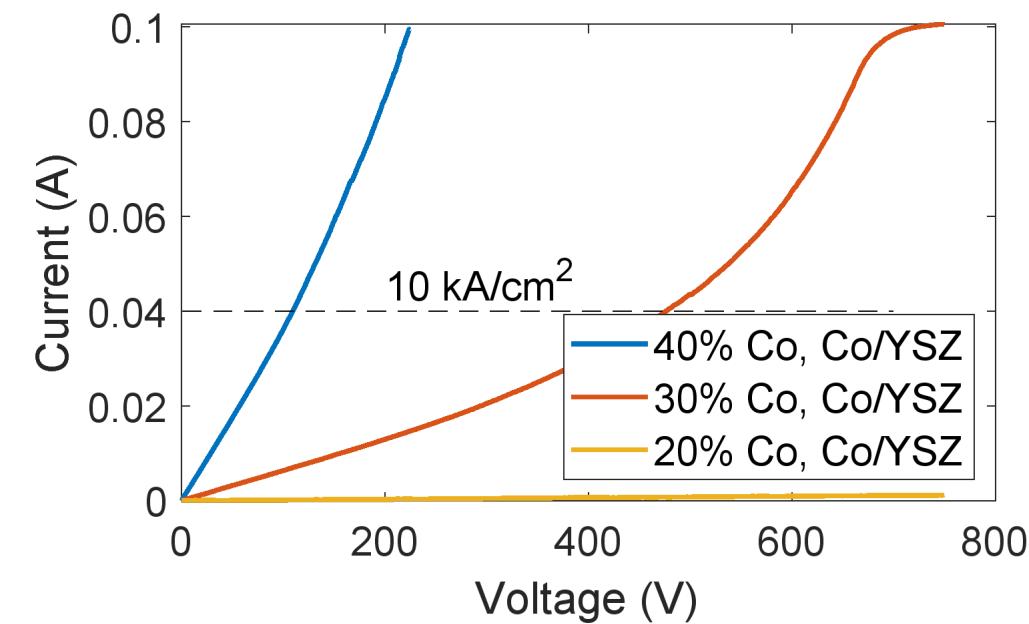
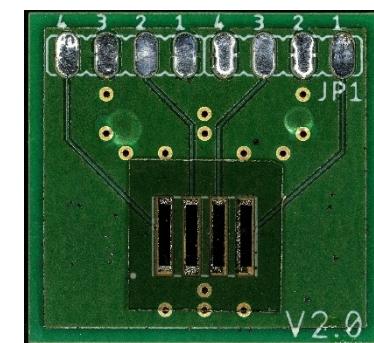
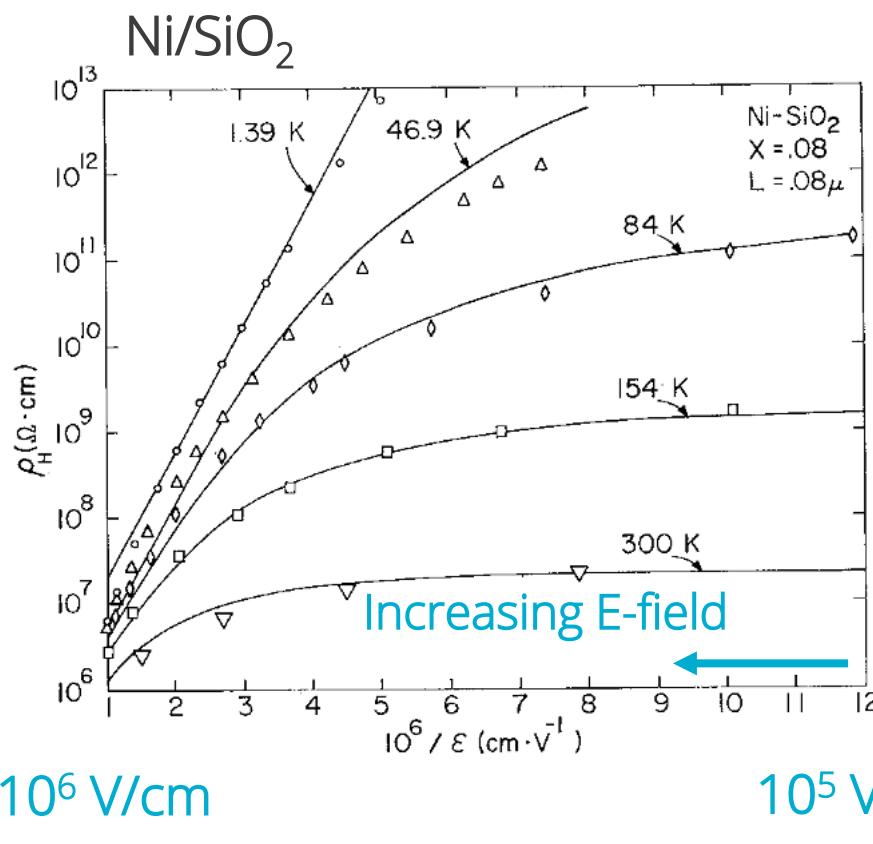
Conductivity change across percolation threshold.

Non-noble metals typically  $10^2$ - $10^3$

Noble metals typically  $\geq 10^4$

# Granular metals are suitable for high E-field applications

- > 5 kV/cm demonstrated in lateral devices
- > 0.1 MV/cm in vertical devices



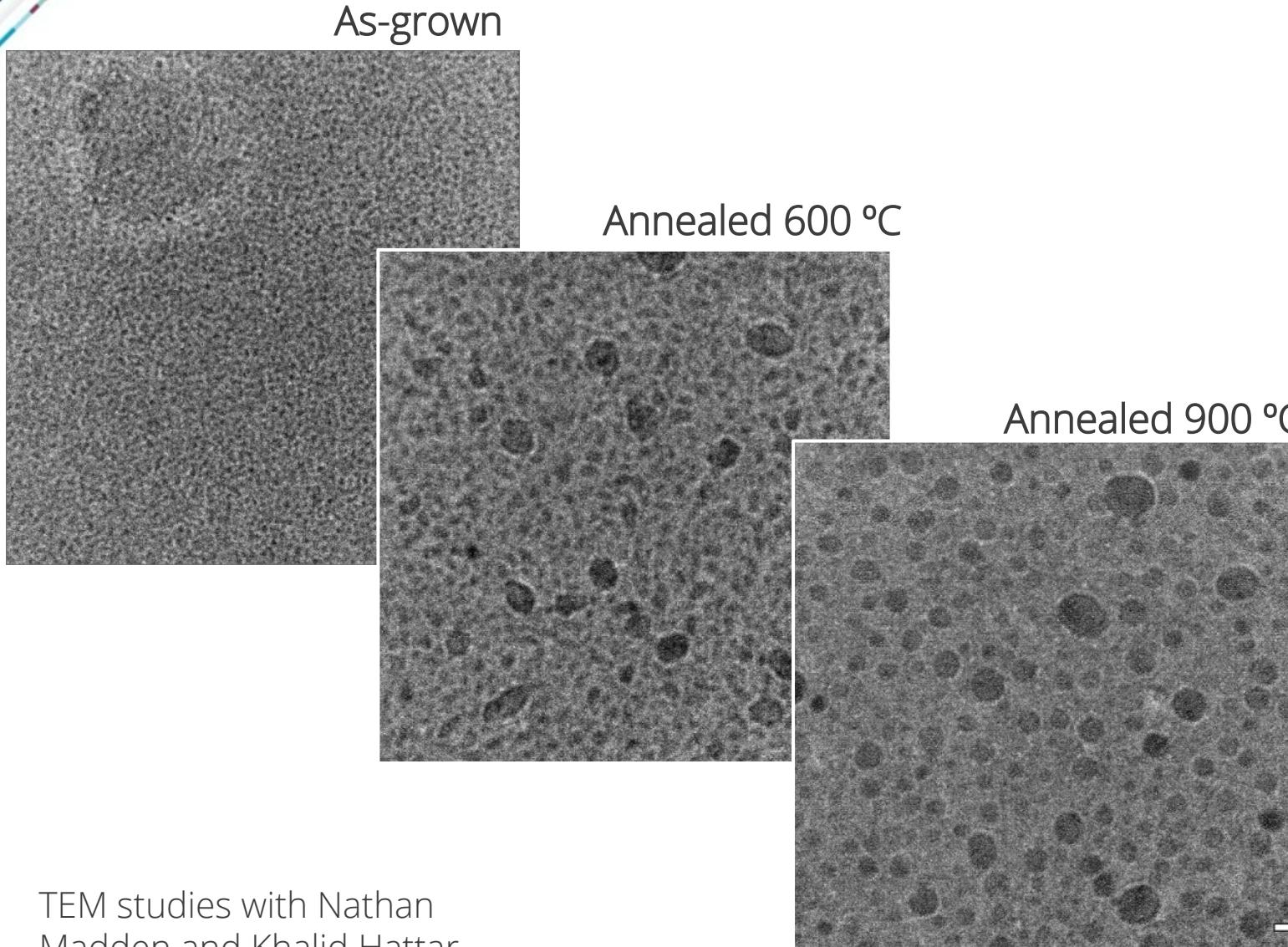
Field-enhanced tunneling

$$\sigma_{H,DC} \propto \exp(\mathcal{E}_0/E) \text{ for } e\Delta V > k_B T$$

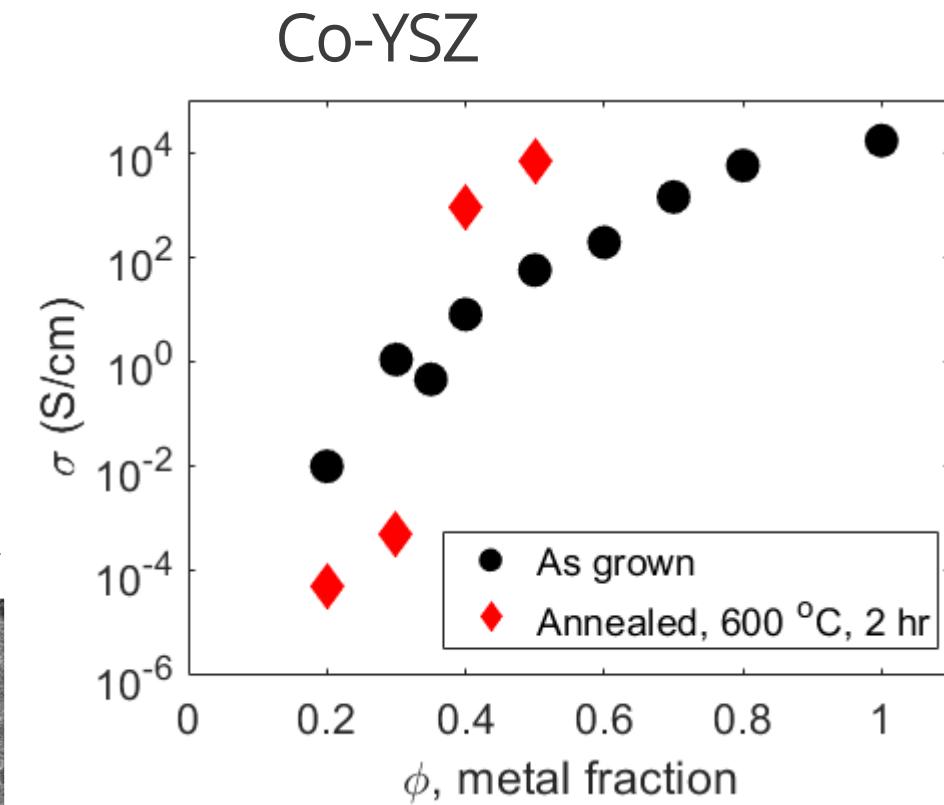
Fowler-Nordheim tunneling

$$\sigma_{FN,DC} \propto \exp(1/E) \text{ for } e\Delta V > \text{tunneling barrier height}$$

# Annealing drives island coalescence and should mitigate interface effects



TEM studies with Nathan  
Madden and Khalid Hattar

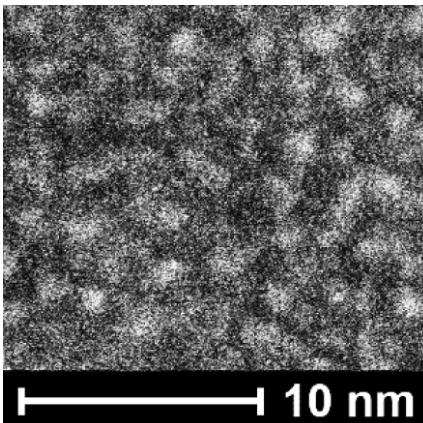


TEM images of 5 nm  
thick Co-YSZ

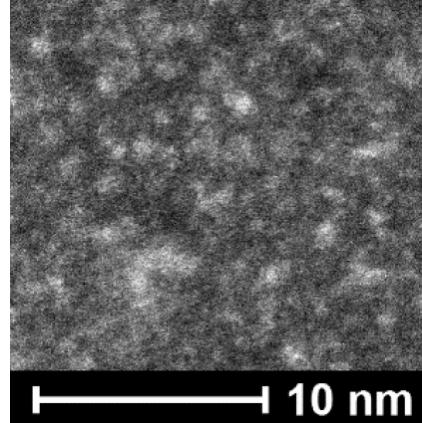
10 nm  
↔

# Conclusion: Controlling interface interactions is crucial for controlling granular metal conductivity

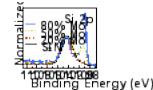
Mo-YSZ,  $\phi = 0.2$



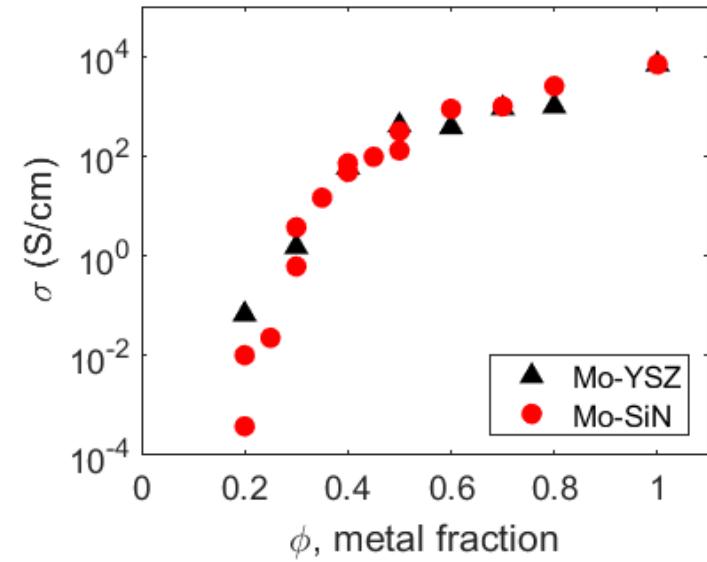
Mo-SiN,  $\phi = 0.2$



Mo-SiN<sub>x</sub>



Mo-silicide formation



## Acknowledgements

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# 80 dB drop in impedance achieved in Mo-SiN granular metal

